L Number	Hits	Search Text	DB	Time stamp
-	79330	silicon adj nitride	USPAT; US-PGPUB	2004/09/10 16:53
-	5648	"Si.sub.3N.sub.4"	USPAT; US-PGPUB	2004/09/10 16:54
-	959	Si3N4	USPAT; US-PGPUB	2004/09/10 16:54
-	346	"Si.sub.xN.sub.y"	USPAT; US-PGPUB	2004/09/10 16:54
-	96	SixNy	USPAT; US-PGPUB	2004/09/10 16:55
-	78856	chemical adj vapor adj deposit$3	USPAT; US-PGPUB	2004/09/10 16:56
-	77927	CVD	USPAT; US-PGPUB	2004/09/10 16:57
-	571	rapid adj thermal adj ((chemical adj vapor adj deposit$3) or CVD)	USPAT; US-PGPUB	2004/09/10 16:57
-	171	remote adj plasma adj enhanced adj ((chemical adj vapor adj deposit$3) or CVD)	USPAT; US-PGPUB	2004/09/10 16:58
-	313	atomic adj layer adj ((chemical adj vapor adj deposit$3) or CVD)	USPAT; US-PGPUB	2004/09/10 16:58
-	815	thermal adj nitridation	USPAT; US-PGPUB	2004/09/10 16:59
-	435	plasma adj nitridation	USPAT; US-PGPUB	2004/09/10 16:59
-	0	((silicon adj nitride) or "Si.sub.3N.sub.4" or Si3N4 or "Si.sub.xN.sub.y" or SixNy) same (rapid adj thermal adj ((chemical adj vapor adj deposit$3) or CVD)) same (remote adj plasma adj enhanced adj ((chemical adj vapor adj deposit$3) or CVD)) same (atomic adj layer adj ((chemical adj vapor adj deposit$3) or CVD)) same (thermal adj nitridation) same (plasma adj nitridation)	USPAT; US-PGPUB	2004/09/10 17:00
-	0	((silicon adj nitride) or "Si.sub.3N.sub.4" or Si3N4 or "Si.sub.xN.sub.y" or SixNy) same (rapid adj thermal adj ((chemical adj vapor adj deposit$3) or CVD)) same (remote adj plasma adj enhanced adj ((chemical adj vapor adj deposit$3) or CVD)) same (atomic adj layer adj ((chemical adj vapor adj deposit$3) or CVD))	USPAT; US-PGPUB	2004/09/10 17:00
-	594	((silicon adj nitride) or "Si.sub.3N.sub.4" or Si3N4 or "Si.sub.xN.sub.y" or SixNy) same ((rapid adj thermal adj ((chemical adj vapor adj deposit$3) or CVD)) or (remote adj plasma adj enhanced adj ((chemical adj vapor adj deposit$3) or CVD)) or (atomic adj layer adj ((chemical adj vapor adj deposit$3) or CVD)) or (thermal adj nitridation) or (plasma adj nitridation))	USPAT; US-PGPUB	2004/09/10 17:19
-	215	((silicon adj nitride) or "Si.sub.3N.sub.4" or Si3N4 or "Si.sub.xN.sub.y" or SixNy) same ((rapid adj thermal adj ((chemical adj vapor adj deposit$3) or CVD)) or (remote adj plasma adj enhanced adj ((chemical adj vapor adj deposit$3) or CVD)) or (atomic adj layer adj ((chemical adj vapor adj deposit$3) or CVD)))	USPAT; US-PGPUB	2004/09/10 17:34

-	0	((silicon adj nitride) or "Si.sub.3N.sub.4" or Si3N4 or "Si.sub.xN.sub.y" or SixNy) same (rapid adj thermal adj ((chemical adj vapor adj deposit$3) or CVD)) same (remote adj plasma adj enhanced adj ((chemical adj vapor adj deposit$3) or CVD)) same (atomic adj layer adj ((chemical adj vapor adj deposit$3) or CVD))	USPAT; US-PGPUB	2004/09/10 17:35
-	1822	atomic adj layer adj deposit$3	USPAT; US-PGPUB	2004/09/10 17:35
-	0	((silicon adj nitride) or "Si.sub.3N.sub.4" or Si3N4 or "Si.sub.xN.sub.y" or SixNy) same (rapid adj thermal adj ((chemical adj vapor adj deposit$3) or CVD)) same (remote adj plasma adj enhanced adj ((chemical adj vapor adj deposit$3) or CVD)) same (atomic adj layer adj deposit$3)	USPAT; US-PGPUB	2004/09/10 17:35
-	4	((silicon adj nitride) or "Si.sub.3N.sub.4" or Si3N4 or "Si.sub.xN.sub.y" or SixNy) same (rapid adj thermal adj ((chemical adj vapor adj deposit$3) or CVD)) same (remote adj plasma adj enhanced adj ((chemical adj vapor adj deposit$3) or CVD))	USPAT; US-PGPUB	2004/09/10 17:39
-	74	((silicon adj nitride) or "Si.sub.3N.sub.4" or Si3N4 or "Si.sub.xN.sub.y" or SixNy) same (remote adj plasma adj enhanced adj ((chemical adj vapor adj deposit$3) or CVD))	USPAT; US-PGPUB	2004/09/10 18:30
-	265	((silicon adj nitride) or "Si.sub.3N.sub.4" or Si3N4 or "Si.sub.xN.sub.y" or SixNy) same ((atomic adj layer adj ((chemical adj vapor adj deposit$3) or CVD)) or (atomic adj layer adj deposit$3))	USPAT; US-PGPUB	2004/09/10 18:30

L Number	Hits	Search Text	DB	Time stamp
1	136406	silicon adj $2oxide	USPAT; US-PGPUB	2004/09/10 19:54
2	134116	"SiO.sub.2"	USPAT; US-PGPUB	2004/09/10 19:54
3	6905	SiO2	USPAT; US-PGPUB	2004/09/10 19:55
4	23545	thermal adj oxidation	USPAT; US-PGPUB	2004/09/10 19:55
5	1234	plasma adj oxidation	USPAT; US-PGPUB	2004/09/10 19:55
6	102	((silicon adj $2oxide) or "SiO.sub.2" or SiO2) same (thermal adj oxidation) same (plasma adj oxidation)	USPAT; US-PGPUB	2004/09/10 19:56